

Film formation of non-planar phthalocyanines on copper (I) iodide

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Electronic Supplementary Information (ESI)

Figure S1 – XRD pattern and AFM image of 50nm ClAlPc/SiO₂ grown at RT

Figure S2- XRD pattern and AFM image of 50nm ClAlPc/30nm CuI/SiO₂ grown at RT

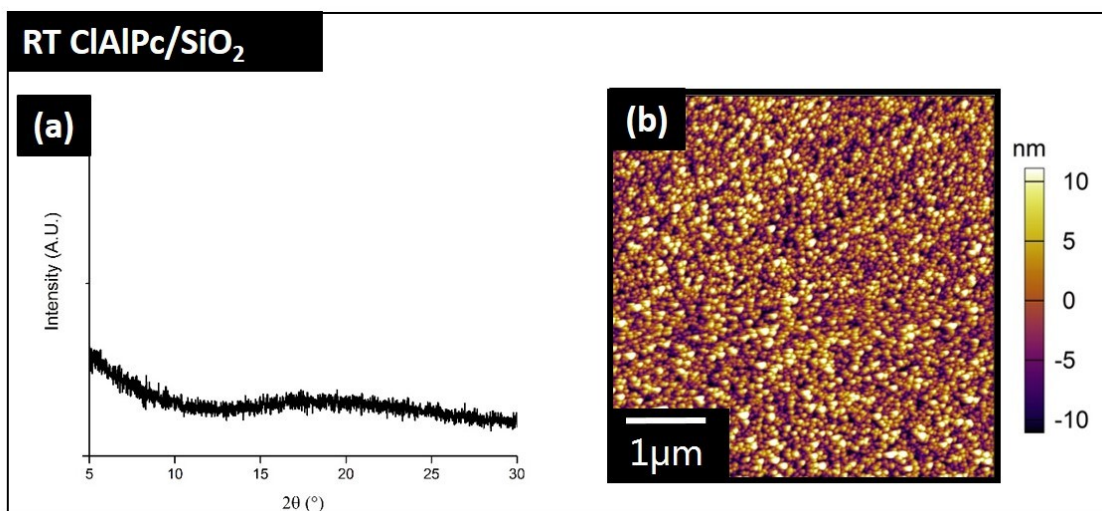


Figure S1 – (a) XRD pattern and (b) AFM topography image of 50nm CIAIPc/SiO₂ grown at a substrate temperature of 25°C.

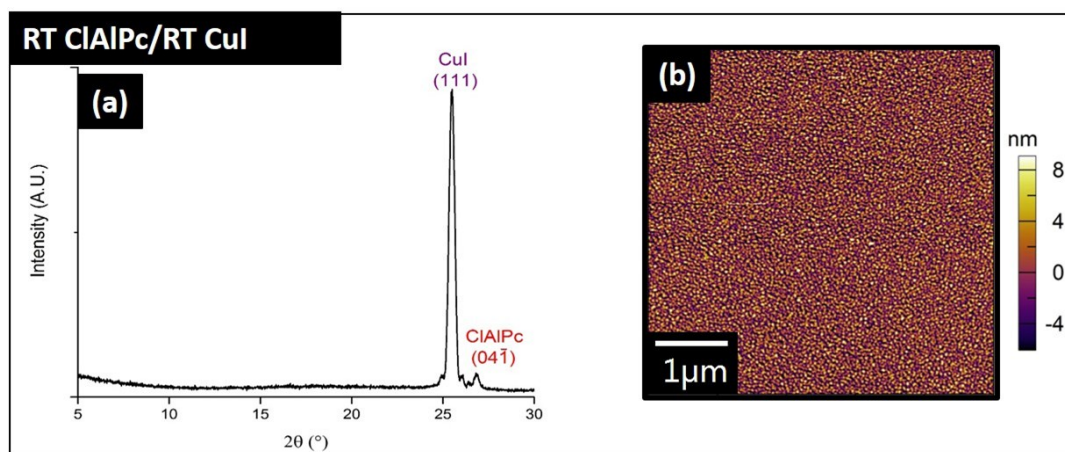


Figure S2 - (a) XRD pattern and (b) AFM topography image of 50nm CIAIPc/30nm CuI/SiO₂ grown at a substrate temperature of 25°C.